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O Device Fabrication Using Soft Lithography Technique V.1

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Protocol status: Working We use this protocol and it's

working

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Abstract

Standard Operating Procedure Institute of Biomedical Engineering University of Toronto

Name of the procedures: Device Fabrication using Soft Lithography Technique

Location: MB308A PI: Dr. Freeman Lan Instructor: Jann Gamboa

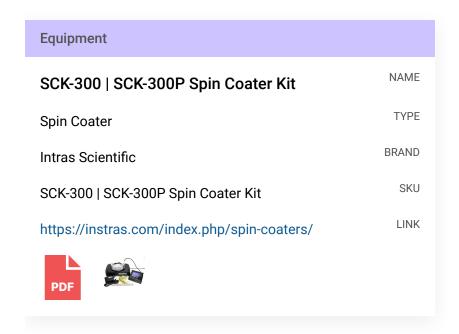
Protocol materials

PDMS Ellesworth Adhesives Catalog #209	99551	In <u>3 s</u>	<u>teps</u>				
PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L In 21 step							
SU-8 3025 Kayaku Advanced Materials Catalog #SU-8 3025 In 8 steps							
Sopropyl Alcohol UofT MedStore Catalog # 934-504-SCA599 In <u>9 steps</u>							
Sylgard-186 Curing Agent Ellesworth Adhesives Catalog #2099551 In 2 steps							
PDMS Base Ellesworth Adhesives Catalog #2099551 In 2 steps							



Potential Hazards

- 1. PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L is a reproductive toxin and goes through gloves!
 - 2. Wear cut resistant gloves when using the razor!
 - 3. Always put the lid on when using the



Note: The wafer could come off and cut you, or

SU-8 3025 Kayaku Advanced Materials Catalog #SU-8 3025 could spray everywhere.

4. Aquapel Amazon Catalog #B084R7LXY5 burns the eyes! Put on safety goggles when using

Equipment Preparation

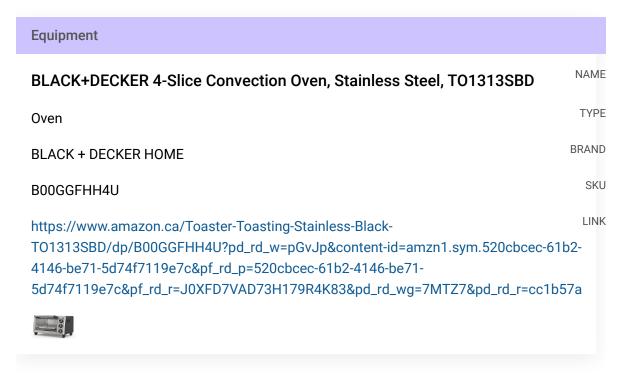
2 Hot Plates and Oven



2.1 The first step consists of turning one hot plate to 4 95 °C and another hot plate to ~

₽ 200 °C

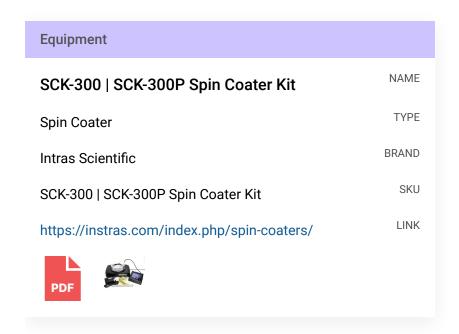
2.2 Turn on the



by turning the timer to "stay on" and the temperature to 4 60 °C.

- 3 **Equipment Checklist:**
 - 1. Tweezers (2)
 - 2. Pyrex dish for the
 - PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L
 - 3. Sopropyl Alcohol **UofT MedStore Catalog #**934-504-SCA599 waste beaker
 - 4. PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L waste beaker
 - 5. SU-8 3025 Kayaku Advanced Materials Catalog #SU-8 3025 solid Waste Container
 - 6. Aluminum foil
 - 7. Double sided tape
 - 8. Glass Slabs (for exposure)
 - 9. Timers

4



- 4.1 Ensure that the spin coater cover and base are covered with aluminum foil.
- 4.2 Ensure that the spin coater is programmed to the desired 2-step rpm (1000 rpm for ♦ 00:00:10 and the appropriate rpm for ♦ 00:00:30 ; refer to Figure 1)

40s

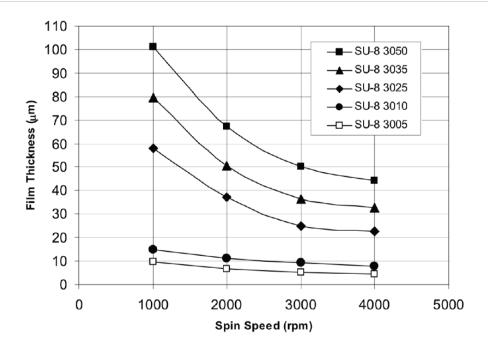


Figure 1. SU-8 3000 Thickness vs. Spin Speed (21°C US & EU)

Figure 1 is from the

- 4.3 Place a piece of double sided tape on the spin coater.The tape should cover the diameter of the spin coater stage and be centered.
- 4.4 Note: There may be times when the tape is not sticking to the spin coater stage. To mitigate this issue, clean the stage with

10m

- 1. Unscrew the stage portion of the spin coater
- 2. Place it on a separate clean beaker.
- 3. Pour PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L onto it, just enough to submerge the surface of the stage. You can obtain the
 - PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L either from the "Used PGMEA bottle" so long as the number of times that it has been recycled is <10. Otherwise, obtain it from the fresh PGMEA squeeze bottle.
- 4. Agitate the beaker gently for 👏 00:05:00



- 5. After 00:05:00, pick up the stage using tweezers and wash it off for the last time with fresh PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L over the same beaker.
- 6. Wash the stage with Stopropyl Alcohol **UofT MedStore Catalog #**934-504-SCA599 over the Isopropyl Alcohol **UofT MedStore Catalog #**934-504-SCA599 waste beaker.
- 7. Blow dry the spin coater stage using the Dyson technique.
- 8. Proceed to place the double sided tape on the spin coater.
- 9. Discard the PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L to the "Fully depleted PGMEA waste bottle".

5

Equipment			
Silicon Wafer	NAME		
SU-8 Substrate	TYPE		
University Wafer	BRAND		
ID-452	SKU		
https://order.universitywafer.com/default.aspx?cat=Silicon⋄=100mm ^{LINK}			

- 5.1 Locate or prepare a beaker for the waste
 - **⊠** Isopropyl Alcohol **UofT MedStore Catalog #**934-504-SCA599
- 5.2 Pick up the silicon wafer using the tweezer located in the fume hood.
- Finse the wafer with Sopropyl Alcohol **UofT MedStore Catalog #**934-504-SCA599.

 Make sure that the Isopropyl Alcohol **UofT MedStore Catalog #**934-504-SCA599 is ending up in the waste beaker for alcohol.



5.4 Subsequently, use compressed air to blow the alcohol off of the wafer (using the Dyson technique; ask Jann or Freeman if you are unsure)

Spin-coating and Soft Baking

6 Centre the silicon wafer on the spin-coater stage.



6.1 Note: It is imperative to centre the silicon wafer onto the spin coater stage as it can lead to uneven coating. If this occurs, proceed to wash off the

5m

SU-8 3025 Kayaku Advanced Materials Catalog #SU-8 3025 on the wafer with

□ PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L for for formal forma

© 00:05:00 using the instructions above over a Pyrex dish, not the beaker.

- Obtain the SU-8 3025 Kayaku Advanced Materials Catalog #SU-8 3025 NOT from the main SU-8 bottle but from the pre-made aliquots.
- Place about 1 mL or 2 mL (the size of a quarter coin) of the

 SU-8 3025 Kayaku Advanced Materials Catalog #SU-8 3025 on the centre of the

 wafer, taking care not to create air bubbles. Make sure also that you do not get any

 SU-8 3025 Kayaku Advanced Materials Catalog #SU-8 3025 on the neck of the bottle

 because it would then be hard to close the bottle.
- 8.1 Note 1: DO NOT let the SU-8 3025 Kayaku Advanced Materials Catalog #SU-8 3025 bottle be open for a longer period of time because the compound quickly evaporates and changes the compound in the bottle.
- 8.2 Note 2: Note that SU-8 3025 Kayaku Advanced Materials Catalog #SU-8 3025 solid wastes should only be placed in the yellow container that is marked "SU-8 Solid Waste"
- Spin the wafer according to the appropriate rpm (1000 for 00:00:10 and refer to Figure 1 for the appropriate rpm for 00:00:30)

40s

10 After spinning, pick up the wafer on its edge and place it on the \$\mathbb{g}\$ 95 °C hot plate for

10m

(5) 00:10:00



- 10.1 Note 1: Make sure that the double sided tape from the spin coater is not stuck on the bottom of the wafer before placing it on the hot plate.
- 10.2 Note 2: Adjust the soft bake times according to the thickness of the channel

THICKNESS microns	SOFT BAKE TIMES minutes @ 95°C
4 –10	2–3
8–15	5–10
20–50	10–15
30–80	10–30
40–100	15–45

Photolithographic Exposure

30s

- 11 Place the wafer and the print out of the mask in between two pieces of glass such that the order is:
 - Glass | wafer | mask | Glass <--- UV Light
- 11.1 Note 1: Make sure that the mask is facing up - that is, the description (writings) on the mask is facing up. You can tell that the mask is facing up if you can read the description.
- 12 Important: Wear the UV glasses.



13 Ensure that the



Equipment

UV Flashlight

UV Flashlight

Alonefire

B09J885Q6N

 $https://www.amazon.ca/Alonefire-Flashlight-Rechargeable-Ultraviolet-Protective/dp/B09J885Q6N/ref=sr_1_12?crid=1W9VMORE03W7W\&dib=eyJ2ljoiMSJ9.Zri-APTD_Oraxzj_1YXHz45WS-$

OoVN9u2B37ltG3nYUWLfH_f8h0nVdvwxBebzlGtLabjz83tH8nmBHrLPpg5SNN_sT2lldTfyn17x

is on full battery, that is, 4/4 bars.

- 14 Place the UV light apparatus over on top of the glasses. Make sure that the box is covering the entirety of the glasses. Make sure that you line up the UV light on the centre of the wafer and the mask.
- 15 Inform everyone in the lab before turning on



16 Expose for 00:00:30

30s

Post-Exposure Baking (PEB)



Heat the wafer again by placing it on the 95 °C hot plate for 00:03:00 to 00:05:00

8m

17.1 Note 1: At this point you should be able to see the outlines of the channel on the wafer. No visible latent image during or after PEB means that there was insufficient exposure, temperature or both.

Channel Development

- 18 For this step, you would need a compound called
 - PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L Locate first the bottle that says "Used PGMEA". If the number of times that the product has been reused is less than 10, proceed to use the "Used PGMEA". Otherwise, use fresh
 - PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L from the squeeze bottle or the actual bottle.
- 18.1 WARNING 1: PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L goes through gloves - make sure that you double glove and/or change your gloves if you feel it necessary
- 18.2 WARNING 2: PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L is a reproductive toxin – it is not good for pregnant women
- 19 Pour PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L onto the Pyrex dish, just enough to submerge the wafer, thereby developing it.
- 19.1 If the PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L used more than 10 times, dispose of it in the PGMEA waste container and obtain it from the original bottle.
- 20 Cover the Pyrex dish using aluminum foil.
- 21 Manually agitate (gentle) the Pyrex dish every once in a while.
- 22 The development time depends on the thickness (height) of the channels. See the table below for guidance.



THICKNESS microns	DEVELOPMENT TIME minutes
4–10	1–3
8–15	4–6
20–50	5–8
30–80	6–12
40–100	7–15

Table 6. Development Times for SU-8 Developer

- After the appropriate development time has passed, take out the wafer using tweezers.
- 24 Rinse the wafer with fresh

Ø PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L (over the Pyrex dish)

- Rinse the wafer with Sopropyl Alcohol **UofT MedStore Catalog #**934-504-SCA599 over the IPA waste beaker
- 26 If white precipitates arise, wash with fresh

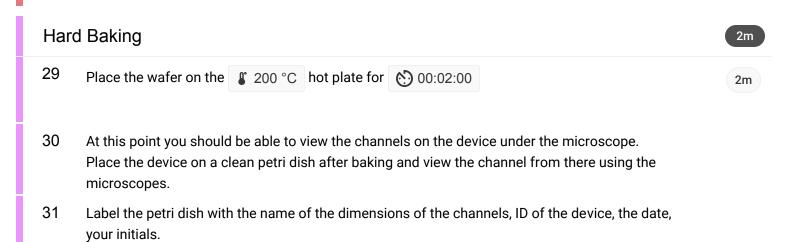
PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L over the PGMEA waster beaker to wash off

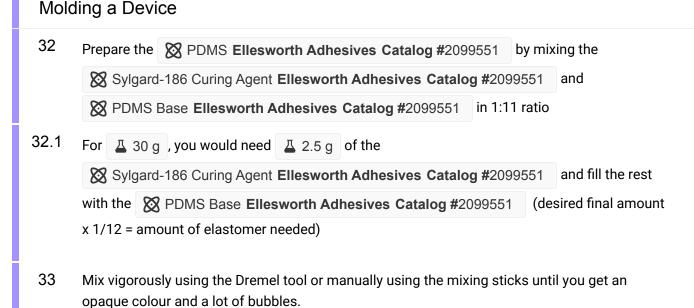
- **26.1** Repeat steps 24-25
- 27 If Sopropyl Alcohol **UofT MedStore Catalog #**934-504-SCA599 doesn't generate white precipitates, then blow dry off using the Dyson technique



- Recycle the PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L by pouring it back to the used PGMEA bottle (use the PGMEA funnel). Indicate that the PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L has been used once more by writing a line on the bottle.
- Note: If the number of lines has reached 10, discard the

 PGMEA Merck MilliporeSigma (Sigma-Aldrich) Catalog #484431-4L in the PGMEA waste container.

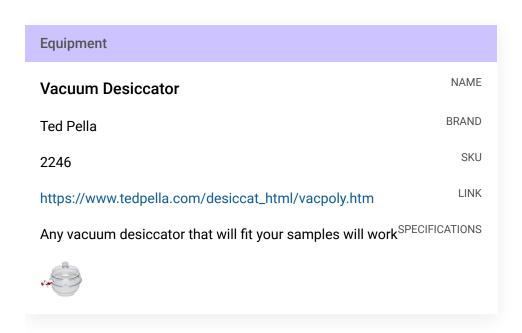




2m



34 Degas or desiccate until the PDMS Ellesworth Adhesives Catalog #2099551 is free from air bubbles using the



- 35 While waiting, place the wafer on a petri dish. Cover it so that it is free from dust.
- 36 Once the de-gassing is done, pour the

PDMS Ellesworth Adhesives Catalog #2099551 on top of the wafer.

- 37 Make sure that the temperature of the oven is around 60 °C. Place it in the oven for several hours or even 🚫 Overnight
- 37.1 Important: since the temperature of the oven fluctuates drastically, place the cover of the petri dish at the bottom by placing the device on top of it so that it does not melt.

Harvesting the Device

- 38 After several hours, take the device out of the oven.
- 39 IMPORTANT: Wear the cut resistant gloves.



- 40 Cut the device mold using a scalpel. Make sure that you are not cutting into the channels and don't push too hard on the wafer or it will splinter
- 41 Peel the device mold using tweezers or your hands
- 41.1 Note 1: It is very easy to break the silicon wafer so when you are cutting or peeling off the device, be very careful not to break the wafer.
- 42 Punch the inlet and outlets of the device using the manual puncher.
- 43 Tape the device so that it would be free from dust.

Plasma Bonding the Device

44 Speak to Jann or Freeman about this or refer to the SOP for the Harrick Plasma Cleaner PDG-32G from the Matsuura Lab

Aquapel Treatment

5m

- 45 IMPORTANT: Wear safety glasses!
- 46 To make the device mold hydrophobic – cut a piece off of the aquapel syringe tubing.
- 47 Stick the tubing into the channel, push just enough to get the liquid into the droplet making a nozzle.
- 48 Push air through the channel to clear it out.
- 49 Put in the oven for 00:05:00 to dry.

5m

50 Seal the aquapel syringe tubing by melting the tubing end for a FEW seconds on the hot plate or lamp and sealing it with your gloved fingers.

